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lithography.wmv Introduction To

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The first step & Scan system

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introduced by ASML was the PAS 5500/500, completed in 1997 and shipping in volume from 1998. See for instance, ASML's 20th anniversary book, REFLECT & IMAGINE - 20 Years of ASML' published by ASML in December 2004.

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ASML - PAS 5500/400, Step & Scan
System

As Architect PAS 5500 Electronics you specify the new rack design, manage the design outsourcing, align the design with the Software Development team, manage the system integration and transfer the

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new design to Customer Support (CS),
Manufacturing and Logistics. Job
Description. The Architect PAS 5500
Electronics is responsible for the
following:

Architect PAS 5500 Electronics - ASML
Description. The PAS 5500/850C

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248-nm Step-and-Scan system enables 110-nm mass production. Since the initial introduction of the PAS 5500/850, the PAS 5500/850 series have become the worldwide standard for both 110-nm logic and 110-nm memory applications. The PAS 5500/850C can be configured

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with a number of options that enable ultra low-k 1in manufacturing, extending application of the PAS 5500/850C well below 110 nm.

PAS 5500/850C - ASML

The ASML PAS 5500/350C stepper is a photolithography equipment, using

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DUV light from a KrF laser source (248 nm) to expose photoresist through a mask, generally referred as the “reticle”. In opposition to a contact/proximity mask-aligner, a projection lens is interposed between the reticle and the wafer in order to reduce (usually by 4x or 5x) the image

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of the reticle onto the wafer.

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ASML PAS 5500/350C CMI EPFL
Architect PAS 5500 Electronics -
asml.com The PAS 5500/850C 248-nm
Step-and-Scan system enables
110-nm mass production. Since the
initial introduction of the PAS

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5500/850, the PAS 5500/850 series have become the worldwide standard for both 110-nm logic and 110-nm memory applications.

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The ASML PAS 5500/60 stepper is an i-

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Alignment And Zero 100mm *
wafer cassette processing capability.
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Using 365nm near-UV light this
stepper is capable of a minimum
feature size of 450nm and alignment
between lithographic layers of 90nm.
The stepper uses 5X reduction
imaging allowing a maximum die

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ASML PAS 5500/60 i-line Stepper
(asml) | Stanford ...

The ASML PAS 5500/350C stepper is a photolithography equipment, using DUV light from a KrF laser source (248

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nm) to expose photoresist through a mask, generally referred as the “reticle”. In opposition to a contact/proximity mask-aligner, a projection lens is interposed between the reticle and the wafer in order to reduce (usually by 4x or 5x) the image of the reticle onto the wafer.

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ASML PAS 5500/350C Center of
MicroNanotechnology CMI EPFL
Lithography Using ASML Stepper
Page 5 INTRODUCTION (cont.) The
ASML PAS 5500 uses wafer alignment
marks that are diffraction gratings.
There are marks for both the x and y

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directions. These marks are illuminated with a HeNe laser at a single wavelength near 632.8nm. The reflected wave exhibits a diffraction pattern of bright

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diyhpl

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ASML: ASM Lithography - PAS
5500/400, Step & Scan System -
ASML's Total Step and Scan Solution
for sub 0.25Um Applications

ASML - PAS 5500/400, Step & Scan
System specification
Within the year, we launched a

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breakthrough platform, the PAS 5500. With its industry-leading productivity and resolution, the PAS 5500 brought on board the key customers that ASML needed to turn a profit. It was a first step to maturity. In 1995, ASML became a fully independent public company, listed on the Amsterdam

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and New York stock exchanges.

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Our history | ASML - Supplying the
semiconductor industry

The PAS 5500/750F DUV Step-and-
Scan system enables 130-nm mass
production using mature 248-nm KrF
technology.

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PAS 5500/750F - asml.com

INTRODUCTION (cont.) The ASML PAS 5500 uses wafer alignment marks that are diffraction gratings. There are marks for both the x and y directions. These marks are illuminated with a HeNe laser at a single wavelength

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ROCHESTER INSTITUTE OF
TECHNOLOGY MICROELECTRONIC ...
Within BL MPS, Design & Engineering
deliver the structural solution to
supports PAS 5500 installed base by
providing refurbished systems,

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Alignment, spare-parts and service to our customers. To extend the support of the PAS 5500 to 2030 and possibly longer, BL MPS will do a full redesign of the PAS 5500 electronics.

Embedded Software Design Engineer
(C, VxWorks, ARM ... - ASML

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Since the initial introduction of the PAS 5500/850, the PAS 5500/850 series have become the worldwide standard for both 110-nm logic and 110-nm memory applications. The PAS 5500/850D can be configured with a number of options that enable ultra low-k 1 in manufacturing,

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extending application of the PAS
5500/850D well below 110 nm.

PAS 5500/850D Datasheet -- ASML
Optics -- Lithography ...

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Cooperative Agreement

EECS-0335765 and by support from
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ASML PAS 5500/60 I-line Stepper |
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3.1 Overview- These instructions
provide an overview of creating

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stepper jobs for the ASML PAS 5500/200. Up to 30 layers can be done in a single job. In a job, Wafer Layout will define how the die are arranged on the wafer and Layer Layout will define the details of each layer. The maximum square field size on the wafer is $X=22\text{mm}$ and

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Semiconductor & Microsystems

4.1 General Description - The ASML PAS 5500/200 is a 5x reduction, i-line stepper set up for exposure of 6 inch wafers using 6 inch reticles. The system has 350nm resolution with a

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0.48-0.60 variable numerical aperture.
The maximum field size on the wafer
is 22x22mm. Overlay capability is
better than 50nm.

R-I-T Title: ASML Stepper
Lithography System -- PAS
5500/400D: The PAS 5500/400D i-line

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Step-and-Scan system has a variable-NA (0.48 to 0.65) 4x projection lens, which, combined with ASML ' s AERIAL Illuminator, provides 280-nm resolution. ASML ' s revolutionary Step-and-Scan stage technology enables...

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This projection printer uses a DUV (248nm) lens column (0.63 N.A.) to provide a 4:1 reduction with an exposure field size up to 22mm square. Minimum feature size is <math><0.20\mu\text{m}</math>.

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Optical Microlithography Proceedings
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